67,200-447; TSMC 00-0890 Serial Number 09/975,855

AMENDMENTS TO THE SPECIFICATION

Shown in Fig. 3 is a schematic cross-sectional diagram of a microelectronic fabrication mask otherwise equivalent to the microelectronic fabrication mask whose schematic cross-sectional diagram is illustrated in Fig. 2, but wherein, in a first instance, the electron beam exposed blanket resist layer 14' has been developed to form a series of patterned resist layers 14a, 14b and 14b 14c.

